

Abstract of the Disclosure:

An optical waveguide is formed on a substrate 11 by the steps of (1) forming an lower clad layer 12, core layer 13, metal mask layer 14 and a photoresist layer 15, (2) patterning the photoresist layer 15 by using a photomask 16, (3) etching and patterning the metal mask layer 14 wider  
5 than a core of required width using the patterned photoresist layer 15, (4) removing the photoresist layer and the metal mask layer 14 after patterning the core layer 13 by using the patterned metal mask layer 14 to form core 13a, (5) forming an upper clad layer 17 on the lower clad layer 12 so as to bury the patterned core 13a.

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